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PATENT NUMBER and
ISSUE DATE

U.S. UTILITY Patent Application

APPL NUM 10073223	FiLING DATE 02/13/2002	CLASS 430	SUBCLASS 270.1	GAU 1782	EXAMINER Lee · S-J
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**APPLICANTS: Nishi Tsunehiro; Nakashima Mutsuo; Tachibana Seiichiro; Funatsu
Kenji;

**CONTINUING DATA VERIFIED:

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** FOREIGN APPLICATIONS VERIFIED:

JAPAN 2001-037247 02/14/2001

JAPAN 2001-037262 02/14/2001

JAPAN 2001-037271 02/14/2001

PG-PUB	DO NOT PUBLISH <input type="checkbox"/>	RESCIND <input type="checkbox"/>
Foreign priority claimed 35 USC 119 conditions met Verified and Acknowledged Examiner's initials		<input type="checkbox"/> yes <input type="checkbox"/> no <input type="checkbox"/> yes <input type="checkbox"/> no
ATTORNEY DOCKET NO KOJIM-446		
TITLE : Polymer, resist composition and patterning process		

U.S. DEPT. OF COMM./PAT. & TM-PTO-436L(Rev. 12-94)

NOTICE OF ALLOWANCE MAILED		Assistant Examiner	CLAIMS ALLOWED	
			Total Claims	Print Claim for O.G
ISSUE FEE		DRAWING		
Amount Due	Date Paid	Sheets Drwg.	Figs.Drwg.	Print Fig.
TERMINAL DISCLAIMER		Primary Examiner		
		PREPARED FOR ISSUE		
		Application Examiner		
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